



Docket No.: 1752-0165P
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Toshitsura CHO et al.

Application No.: 10/779,680

Confirmation No.: 008556

Filed: February 18, 2004

Art Unit: 1755

For: ABRASIVE SLURRY HAVING HIGH
DISPERSION STABILITY AND
MANUFACTURING METHOD FOR A
SUBSTRATE

Examiner: M. A. Marcheschi

AMENDMENT IN RESPONSE TO FINAL OFFICE ACTION

MS AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INTRODUCTORY COMMENTS

In response to the Office Action dated December 8, 2005, please amend the above-identified U.S. patent application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 4 of this paper.